

Precision and Vacuum Technology



## 032 PRIMS

Simple and full functional sputter deposition system  
for reproducible thin film layers applying

## 032 PRIMS - smart, basic DC sputtering system

Magnetron sputtering sources (for metals and inorganics) are included, mounted in sputter-down configuration. System includes a turbomolecular pump with manual throttle valve. Small process chamber size allows to reach the base pressure in a short time. Dedicated deposition rate checking system is available.



- Compact size design
- Process chamber diameter: Ø 355 mm
- Ports for up to three 2" magnetron sources
- Internal shield against chamber contamination
- Base pressure range  $10^{-7}$  mbar
- Fast turbo-molecular pumping system
- Substrate stage for up to 2" diameter samples
- Process chamber with in full size vacuum door for easy target or substrate replacement

Options:

- Substrate heating up to 600 °C
- Sample/substrate stage rotation
- Deposition rate measurement
- Co-deposition
- Process automation



### MS2 100 ISO-K Magnetron Source

- Mounting flange: DN 100 ISO-K
- Pneumatic dome type shutter
- Chimney as standard

Targets:

- Diameter: 2"
- Thickness | non-magnetic: 1 - 6 mm
- Thickness | magnetic: Fe 1 mm, Co 2-3 mm, Ni 2 mm
- Indirectly cooled



### M600DC-PS DC Power Supply

- Switch for 3 magnetron sources with shutters control
- Power 600 W. Expandable up to 2400 W
- Arc detection system
- Multiple I/O - individual programmable
- Adjustable limits of voltage, current and power separately for each output

Support for:

- Thickness and evaporation rate measurements
- Vacuum measurements
- Mass Flow Controller



If you need any further information, please do not hesitate to contact our sales department

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